**16<sup>th</sup> (Virtual) Workshop on Advanced Silicon Radiation Detectors** Trento, Italy. February 16-18 2021

# TCAD numerical simulation of irradiated Low-Gain Avalanche Diodes

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#### Outline

#### Motivations

- TCAD simulation of LGAD devices
  - Layout and doping profile
  - □ Physical models (e.g. avalanche) and parameters
- Methodology
  - □ Static (DC) and small-signal (AC) behavior
  - Transient response
- Application of the developed model (e.g. thin LGADs)

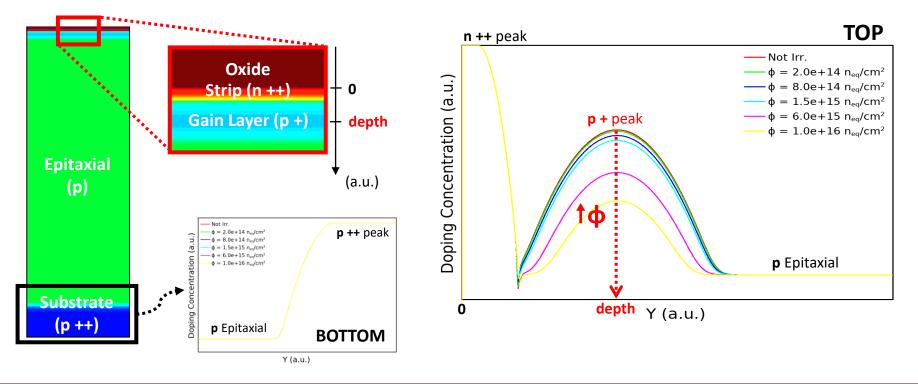
#### **Motivations**

- ✓ Low-Gain Avalanche Diode (LGAD)
- The intrinsic multiplication of the charge allows to improve the signal to noise ratio
   => limitation of its drastic reduction with fluence.
- Most promising devices to cope with the high fluences expected in the future HEP experiments.
- Device-level simulation tools<sup>[1]</sup> for predicting the electrical behaviour and the charge collection properties up to the highest particle fluences.
- ✓ Implementation of a proper radiation damage model within the simulation environment.



### TCAD simulation of LGAD devices (1/2)

#### ✓ Layout and doping profile





## TCAD simulation of LGAD devices (2/2)

#### ✓ Physical models

#### Generation/Recombination rate

- Shockley-Read-Hall (SRH), Band-To-Band Tunneling (BTBT), Auger
- Avalanche Generation

   > impact ionization models, such as
   van Overstraeten-de Man, Okuto-Crowell,
   Massey<sup>[2]</sup>, UniBo
- Carriers mobility variation doping and field dependent
- ✓ Physical parameters
  - e-/h+ recombination lifetime
  - surface recombination velocity

**[2]** M. Mandurrino et al., *Numerical Simulation of Charge Multiplication in Ultra-Fast Silicon Detectors (UFSD) and Comparison with Experimental Data*, IEEE, 2017

- ✓ Radiation damage models
- ✓ "New University of Perugia model"
  - Combined surface and bulk TCAD damage modelling scheme<sup>[3]</sup>
  - Traps generation mechanism
- ✓ Acceptor removal mechanism

 $N_{GL}(\phi) = N_A(0)e^{-c\phi}$ 

where

- Gain Layer (GL)
- c, removal rate, evaluated using the Torino parameterization<sup>[4]</sup>

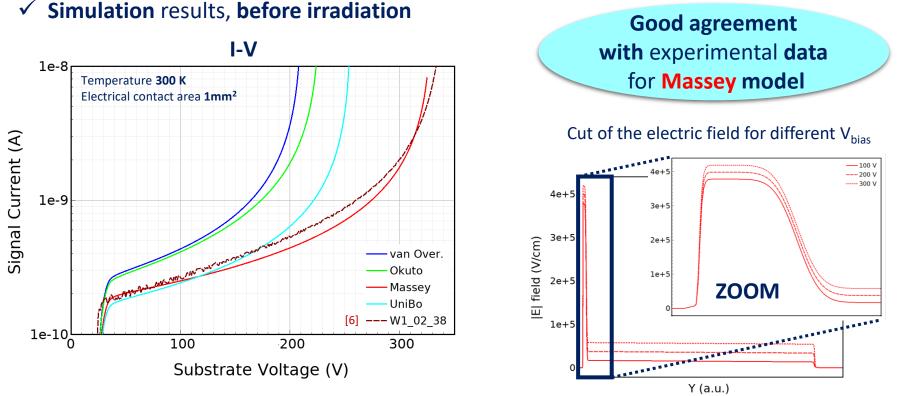
[3] AIDA2020 report, <u>TCAD radiation damage model - CERN Document Server</u>[4] see M. Ferrero talk



#### Methodology



### Analysis of different avalanche models

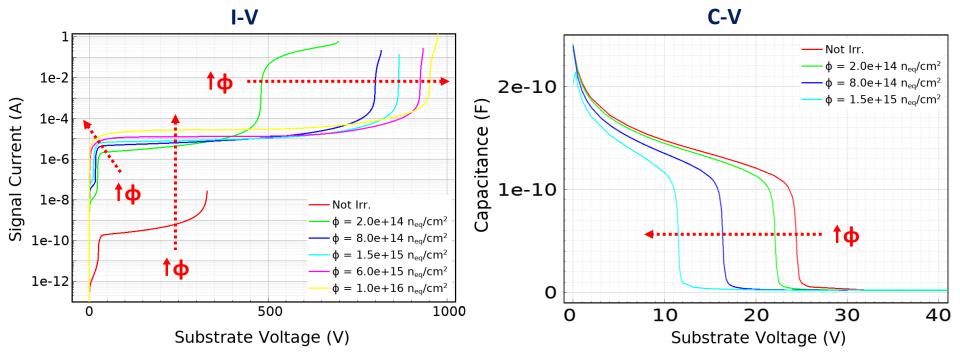


[6] V. Sola et al., *First FBK production of 50 μm ultra-fast silicon detectors*, Nucl. Instrum. Methods Phys. Res. A, 2019

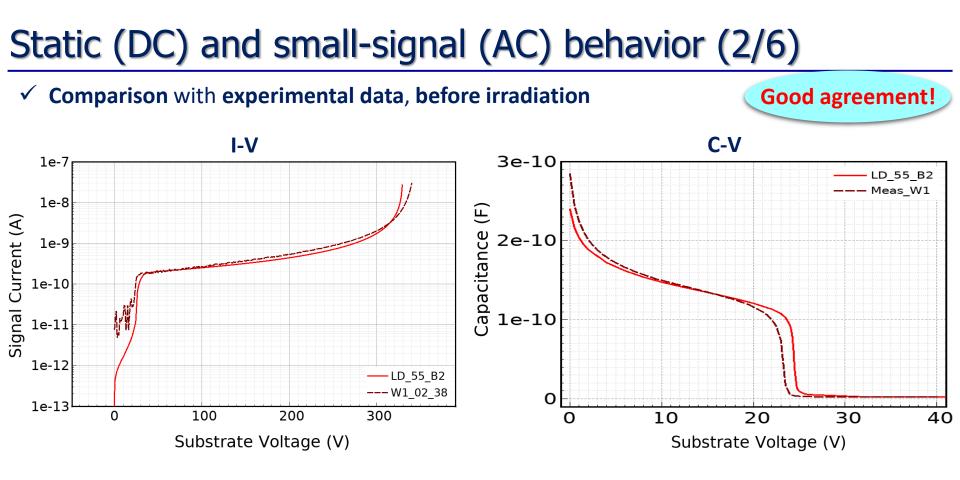


## Static (DC) and small-signal (AC) behavior (1/6)

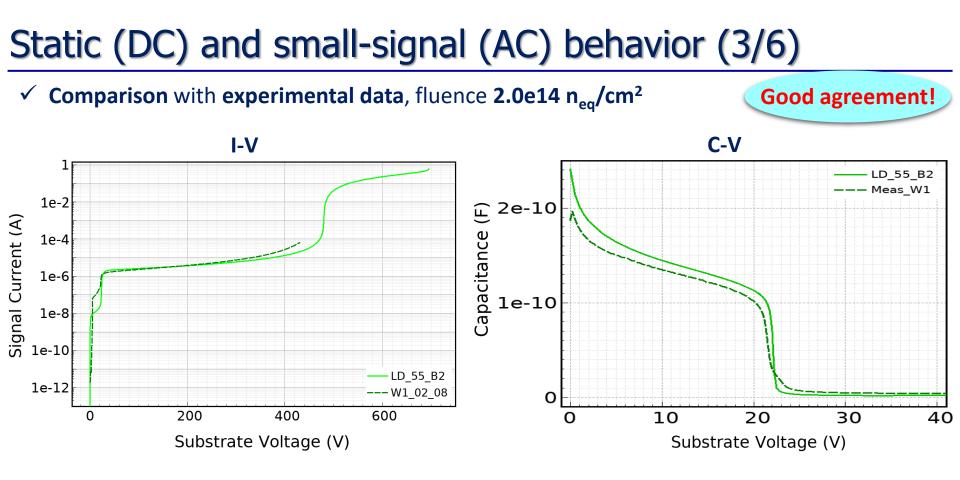
✓ Simulation results, before and after irradiation



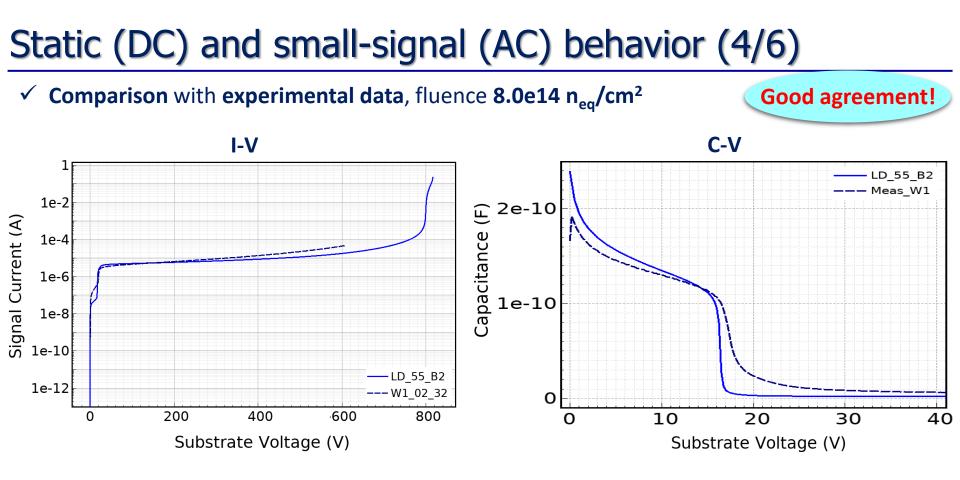




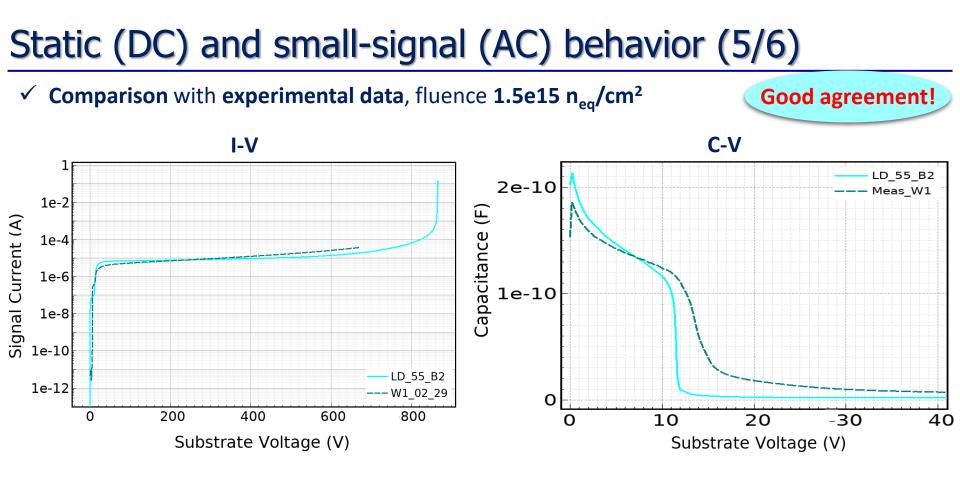










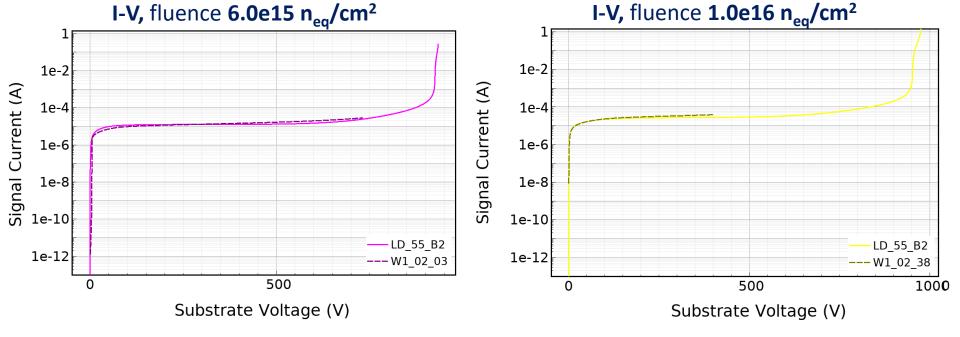




## Static (DC) and small-signal (AC) behavior (6/6)

✓ Comparison with experimental data, after irradiation

Good agreement!



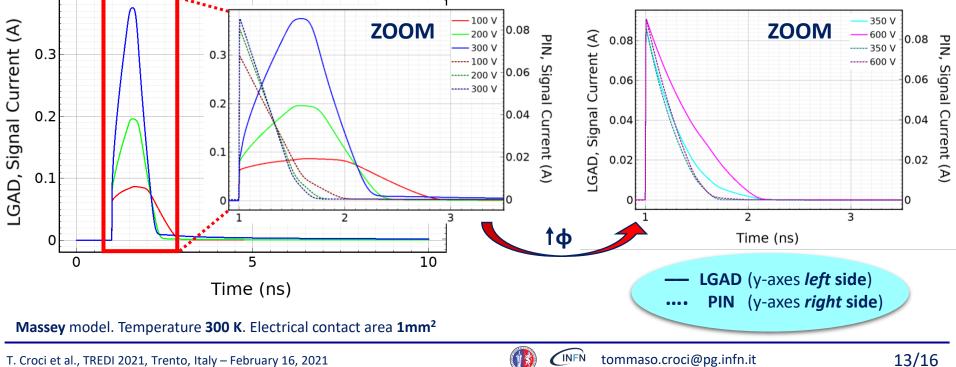


#### Transient response

Comparison between LGAD and PIN response to the MIP for different V<sub>bias</sub>  $\checkmark$ 

I-t, before irradiation

I-t, fluence 1.5e15 n<sub>eq</sub>/cm<sup>2</sup>

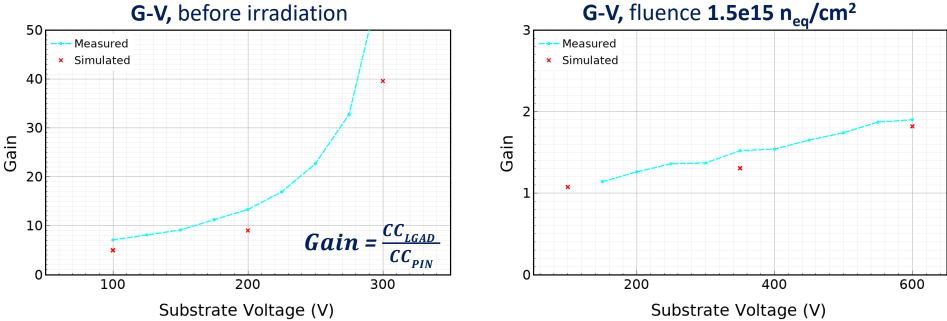


T. Croci et al., TREDI 2021, Trento, Italy – February 16, 2021

### Gain calculation

#### Estimated error on data ±10 % $\checkmark$

**Good** agreement!



**G-V**, before irradiation



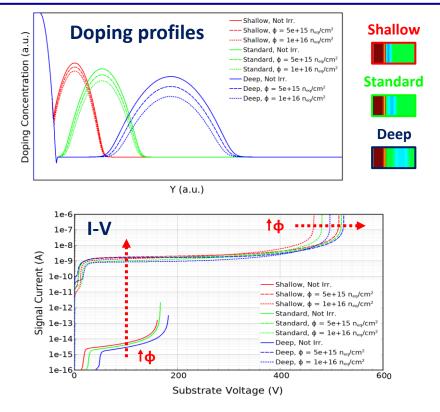
### Application of the developed model

- ✓ Thin wafers recently produced by FBK
  - thickness 25 and 35 μm [7]
- ✓ TCAD simulations very useful to
  - compare the results with the experimental data, before and after irradiation (irradiation campaign just completed at the

Ljubljana JSI facility up to 1.0e17  $n_{eq}$ /cm<sup>2</sup>)

 designing the future productions of thin LGADs for extreme fluences

**[7]** V. Sola et al., *First results from thin silicon sensors for extreme fluences*, 37<sup>th</sup> RD50 Workshop, Zagreb, Croatia, 2020



#### Massey model, Temperature 300 K.



#### Conclusions

- ✓ **Strategy** for the numerical simulation of LGAD devices.
- ✓ **Results** obtained under **different operative conditions** (device biasing, fluence).
- Good agreement between simulation predictions and experimental data for both non-irradiated and irradiated LGAD device.
- Combination of "new University of Perugia TCAD model" and the "acceptor removal" analytical model is used to simulate the radiation damage effects

=> successful **description** of the **decrease in gain with** an increase in **fluence**.

- Application of the validated simulation framework for the prediction of different design options/detector geometries (e.g. thin sensors) behavior
  - => optimization for their use in the future HEP experiments.





Thank you for the attention!

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# BACKUP SLIDES

### Low-Gain Avalanche Diodes (LGADs)

- Most promising devices to cope with the high spatial density of particles hits due to the increasing radiation fluence expected in the HL-LHC at CERN.
- LGAD structure: pin diode with the additional inclusion of a p+-type layer just below the ncontact, which is commonly called *multiplication layer*.
- > By applying a reverse-bias, this layer is responsible for a **multiplication of carriers**.

$$G_{\text{aval}} = \boldsymbol{\alpha}_{n} n \boldsymbol{v}_{n} + \boldsymbol{\alpha}_{p} p \boldsymbol{v}_{p}$$
  $\boldsymbol{\alpha} = \frac{E}{E_{th}} e^{-\frac{E_{t}}{E_{th}}}$ 

- By accurately chosing the peak and shape of the implanted p+ profile, it is possible to control the avalanche mechanism in order to obtain the required internal gain with a sufficiently high breakdown voltage.
- One of the best tools for predicting the behaviour of the avalanche process is device-level simulation

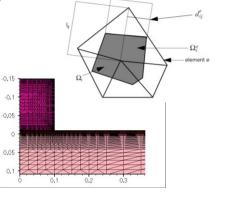


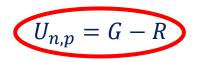
### **Technology-CAD** simulations

- TCAD simulation tools solve fundamental, physical partial differential equations, such as diffusion and transport equation for discretized geometries (finite element meshing).
- > This deep physical approach gives TCAD simulation **predictive accuracy**.
- Synopsys© Sentaurus TCAD

$$\begin{cases} \nabla \cdot (-\varepsilon_s \nabla \phi) = q \quad (N_D^+ - N_A^- + p - n) \\ \frac{\partial n}{\partial t} - \frac{1}{q} \nabla \cdot \vec{J_n} = U_n \\ \frac{\partial p}{\partial t} + \frac{1}{q} \nabla \cdot \vec{J_p} = U_p \end{cases}$$

$$\vec{J}_n, \vec{J}_p$$







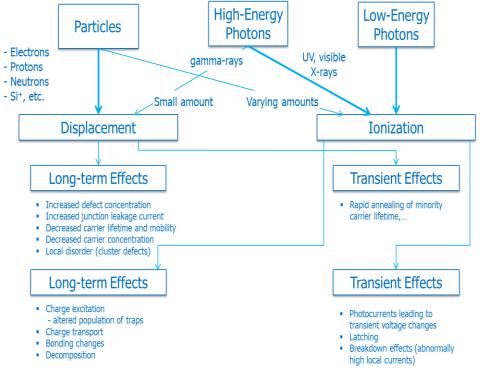
Poisson

**Electron continuity** 

Hole continuity

## Radiation damage effects (1/2)

#### $\checkmark$ in silicon sensors



Two main **types of radiation damage** in detectors materials:

- SURFACE damage => Ionization
  - ✓ Build-up of trapped charge within the oxide;
  - Bulk oxide traps increase;
  - Interface traps increase;
  - ✓ Q<sub>ox</sub>, N<sub>IT</sub>.
- BULK damage => Atomic displacement
  - ✓ Silicon lattice defect generations;
  - Point and cluster defects;
  - ✓ Deep-level trap states increase;
  - Change of effective doping concentration;

✓ N<sub>T</sub>.



### Radiation damage effects (2/2)

#### $\checkmark$ in LGAD devices

- Acceptor removal mechanism [1]: the active (substitutionals) doping elements are partially removed from their lattice sites due to the ionizing radiation and then de-activated after a kick-out reaction (Watkins mechanism [2]) that produces ion-acceptor complexes (interstitials)
- Transformation of electrically active acceptors into defect complexes that no longer have dopant properties
- This has been recently suggested as a possible explanation for the significant degradation of gain (charge multiplication) observed on LGAD devices after irradiation.

- (1) G. Kramberger, M. Baselga et al., J. Inst., vol. 10, no. 7, p. P07006, 2015
- (2) G. D. Watkins, *Defects and Their Structure in Non-metallic Solids*, B. Henderson and A. E. Hughes, Eds. New York: Plenum, 1975



### TCAD radiation damage models used

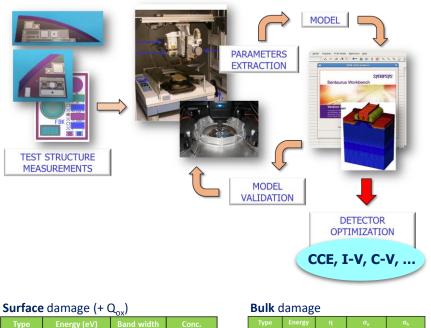
#### "New University of Perugia model"

- Combined surface and bulk TCAD damage modelling scheme
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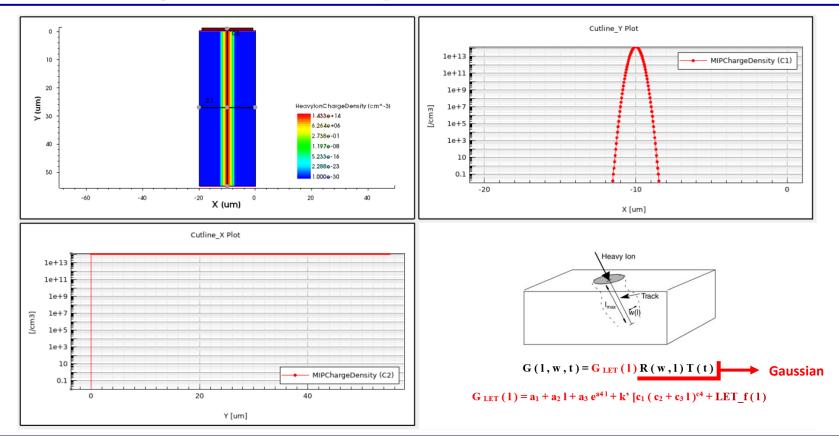


Туре	Energy (eV)	Band width (eV)	Conc. (cm <sup>-2</sup> )
Acceptor	$E_C \le E_T \le E_C$ -0.56	0.56	$D_{IT} = D_{IT}(\Phi)$
Donor	$E_V \le E_T \le E_V$ +0.6	0.60	$D_{IT} = D_{IT}(\Phi)$

Туре	Energy (eV)	η (cm <sup>-1</sup> )	σ <sub>n</sub> (cm²)	σ <sub>h</sub> (cm²)
Donor	E <sub>C</sub> - 0.23	0.006	2.3×10 <sup>-14</sup>	2.3×10 <sup>-15</sup>
Acceptor	E <sub>C</sub> - 0.42	1.6	1×10 <sup>-15</sup>	1×10 <sup>-14</sup>
Acceptor	E <sub>C</sub> - 0.46	0.9	7×10 <sup>-14</sup>	7×10 <sup>-13</sup>



#### Transient responce: "HeavyIon" model





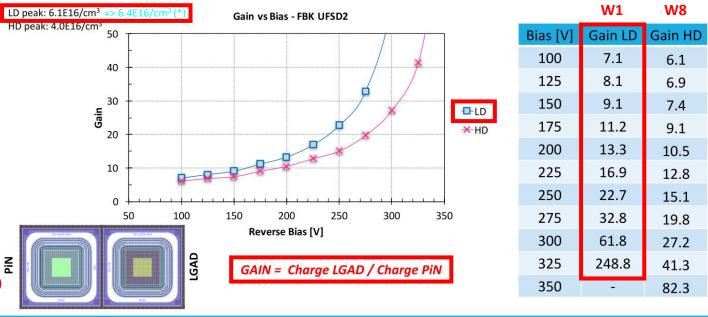
#### Pre-Irradiation: Experimental Data (FBK UFSD2 Production)





TCT Setup from Particulars Pico-second IR laser at 1064 nm Laser spot diameter ~ 50 μm Cividec Broadband Amplifier (40dB) Oscilloscope Lecroy 640Zi Room temperature Laser attenutation 82% (3 MIP 150 fC)





#### SIMULATION PLAN



V. Sola

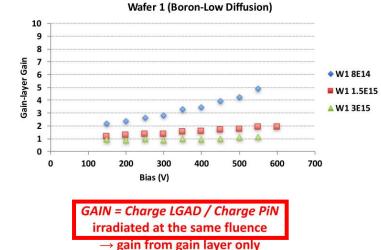


#### Post-Irradiation: Experimental Data (FBK UFSD2 Production)





TCT Setup from Particulars Pico-second IR laser at 1064 nm Laser spot diameter ~ 50 μm Cividec Broadband Amplifier (40dB) Oscilloscope Lecroy 640Zi Room temperature Laser attenutation 82% (3 MIP 150 fC)



Bias [V]	Gain		
	$\Phi$ =8E14	Φ=1.5E15	
150	2.1	1.14	
200	2.4	1.26	
250	2.7	1.36	
300	2.8	1.37	
350	3.3	1.52	
400	3.4	1.54	
450	3.9	1.65	
500	4.2	1.74	
550	4.9	1.87	
600	-	1.90	

**W1** 



SIMULATION PLAN

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V. Sola

